

# Layout Dependent Effect Setup Usage

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OD

WELL

## **Layout Dependent Effect**

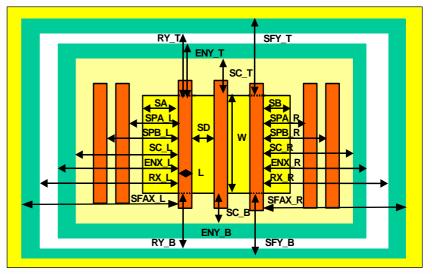
#### Concept

 Define layout dependent effect (LDE) parameters by layer boundary and calculate effective parameters in pre-layout stage

#### Method

- New adjustable parameters based on layout geometry are added into device CDF for layout dependent effect calculation
- User preset function is provided for customer's pre-defined values
- Utility is provided to allow user to specify those parameters by selected instance.

#### **New CDF Parameters**

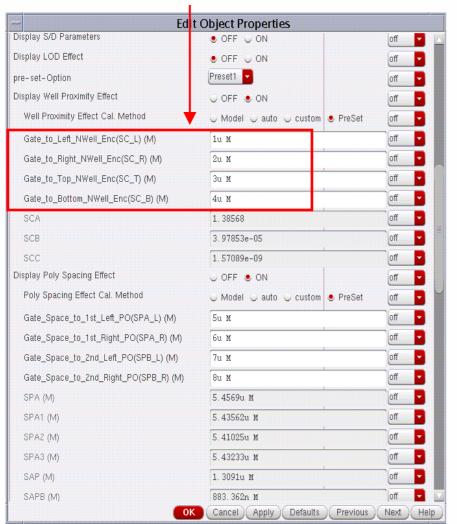


- \* 20 new CDF paramaters are introduced:
- (a) PSE: SPA\_L, SPA\_R, SPB\_L, SPB\_R
- (b) WPE: SC\_L, SC\_R, SC\_T, SC\_B
- (c) BE: ENX\_L, ENX\_R, ENY\_T, ENY\_B, RX\_L, RX\_R, RY\_T, RY\_B
- (d) OSE: SFAX\_L, SFAX\_R, SFY\_T, SFY\_B

## **WPE** parameters



#### Add SC\_L, SC\_R, SC\_T, SC\_B CDF parameters



TION INTOUT I	elated input i	n CDF	parameters	ndent effect	
SPA L. SPA R	SPB L SPB		, ,	. ,	AP, SA4,
SC_L, SC_R, S	C_T, SC_B		SCA, SCB, SC	XC	
		Y_B, RX_L,	ENX, ENX1 REY	NY, ENY1, I	ENY2, REX,
SFAX_L, SFA	K_R, SFY_T, S			1, SODX2, S	A5, SA6,
I	SC_L, SC_R, S ENX_L, ENX_ RX_R, RY_T,	SC_L, SC_R, SC_T, SC_B ENX_L, ENX_R, ENY_T, EN RX_R, RY_T, RY_B	SPA_L_SPA_R_SPB_L_SPB_R SC_L, SC_R, SC_T, SC_B ENX_L, ENX_R, ENY_T, ENY_B, RX_L, RX_R, RY_T, RY_B	SPA I, SPA R, SPB I, SPB R         SPBA, SPBA, SPBA           SC_L, SC_R, SC_T, SC_B         SCA, SCB, SC           ENX_L, ENX_R, ENY_T, ENY_B, RX_L, ENX, ENXI         REY           RX_R, RY_T, RY_B         SODX, SODX	SC_L, SC_R, SC_T, SC_B SCA, SCB, SCC ENX_L, ENX_R, ENY_T, ENY_B, RX_L, ENX, ENX_ENY, ENY1, 1 RX_R, RY_T, RY_B REY SODX, SODX1, SODX2, Sc

Calculate effective SCA, SCB, SCC

 $Ex : SCA_{eff} = f (W, L, NF, SD, SC_L, SC_R, SC_T, SC_B)$ 

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# **PSE** parameters



## Add SPA\_L, SPA\_R, SPB\_L, SPB\_R CDF

— Edit	Object Properties	
Gate_to_Left_NWell_Enc(SC_L) (M)	lu M	off 🔽
Gate_to_Right_NWell_Enc(SC_R) (M)	2u M	off 🔽
Gate_to_Top_NWell_Enc(SC_T) (M)	Зи м	off
Gate_to_Bottom_NWell_Enc(SC_B) (M)	4u M	off 🔽
SCA	1. 38568	off 🔽
SCB	3.97853e-05	off 🔽
scc	1.57089e-09	off
Display Poly Spacing Effect	U OFF ● ON	off 🔽
Poly Spacing Effect Cal. Method	U Model U auto U custom ● PreSet	off 🔽
Gate_Space_to_1st_Left_PO(SPA_L) (M)	Su M	off 🔽
Gate_Space_to_1st_Right_PO(SPA_R) (M)	6u M	off 🔽
Gate_Space_to_2nd_Left_PO(SPB_L) (M)	7u M	off 🔽
Gate_Space_to_2nd_Right_PO(SPB_R) (M)	8u M	off 🔽
SPA (M)	5.4569u M	off 🔽
SPA1 (M)	5.43562u M	off 🔻
SPA2 (M) PSE	5.41025u M	off 🔽
SPA3 (M)	5.43233u M	off 🔽
SAP (M)	1.3091u M	off 🔽
SAPB (M)	883.362n M	off
SPBA (M)	3.29036u M	off 🔽
SPBA1 (M)	3.29283u M	off 🔽
SA4 (M)	75.0n M	off 🔽
Display Boundary Effect	U OFF ● ON	off
Boundary Effect Cal. Method		off
ОК	Cancel Apply Defaults Previous	Next Hel

	New la	yout related input in CD		layout depender parameters	nt effect instance
PSE	SPA_L,	SPA_R, SPB_L, SPB_R		SPA, SPA1, SPA2, SPBA, SPBA1, SA	, SPA3, SAP, SA4, PB
WPE	SC_L, S	C_R, SC_T, SC_B	•	SCA, SCB, SCC	
		ENX_R, ENY_T, ENY_B,	RX_L,		ENY1, ENY2, REX,
BE (D-CESL)	RX_R,	RY_T, RY_B		REY	
				SODX, SODX1, S	DDX2, SA5, SA6,
OSE	SFAX_	., SFAX_R, SFY_T, SFY_B		SODY	

 PSE (Poly Spacing Effect) parameters are adjustable in CDF for callback calculation

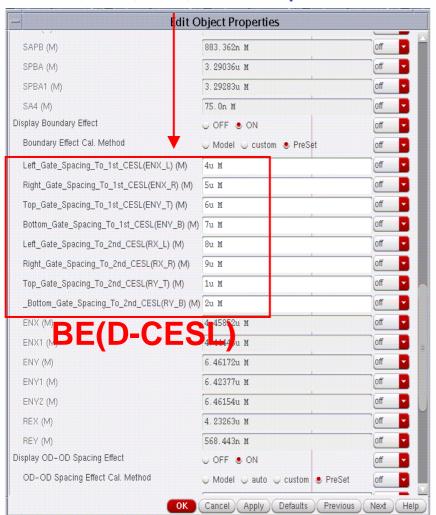
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# **Boundary Effect parameters**



Add ENX\_L,ENX\_R,ENY\_T,ENY\_B,

RX\_L,RX\_R,RY\_T,RY\_B CDF parameters



	New layout related input in CDF	layout dependent effect instance parameters
PSE WPE	SPA_L, SPA_R, SPB_L, SPB_R SC_L, SC_R, SC_T, SC_B	SPA, SPA1, SPA2, SPA3, SAP, SA4, SPBA, SPBA1, SAPB SCA, SCB, SCC
BE (D-CESL)	ENX_L, ENX_R, ENY_T, ENY_B, RX_L, RX_R, RY_T, RY_B	NX, ENX1, ENY, ENY1, ENY2, REX, EY
OSE	SFAX_L, SFAX_R, SFY_T, SFY_B	SODX, SODX1, SODX2, SA5, SA6, SODY

 BE (D-CESL Effect) parameters are adjustable in CDF for callback calculation

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# **OSE** parameters



# Add SFAX\_L, SFAX\_R, SFY\_T, SFY\_B CDF parameters

− Edit C	Object Properties	
_Bottom_Gate_Spacing_To_2nd_CESL(RY_B) (M	) 2u M	off 🔽
ENX (M)	4.45852u M	off
ENX1 (M)	4.44446u M	off 🔻
ENY (M)	6.46172u M	off 🔽
ENY1 (M)	6.42377u M	off 🔻
ENY2 (M)	6.46154u M	off 🔻
REX (M)	4.23263u M	off 🔽
REY (M)	568.443n M	off 🔽
Display OD-OD Spacing Effect	U OFF ● ON	off
OD-OD Spacing Effect Cal. Method	✓ Model ∪ auto ∪ custom ● PreSet	off
Gate_Space_to_Left_OD_edge(SFAX_L) (M)	9u M	off 🔽
Gate_Space_to_Right_OD_edge(SFAX_R) (M)	lu M	off 🔽
Gate_Space_to_Top_OD_edge(SFY_T) (M)	2u M	off 🔽
Gate_Space_to_Bottom_OD_edge(SFY_B) (M)	3u M	off 🔽
SA5 (M)	75.0n M	off 🔽
SA6 (M) OSE	75. On M	off 🔽
SODX (M)	2.1173u M	off 🔽
SODX1 (M)	401.747n M	off 🔽
SODX2 (M)	1.11446u M	off 🔽
SODY (M)	2.42449u M	off 🔽
dW1 (M)	O M	off 🔽
Display DFM Options	● OFF ○ ON	off 🔽
Display Layout Related Parameters	• OFF U ON	off 🔻

	New layout related input in CDF		layout dependent effect instance parameters
PSE	SPA_L, SPA_R, SPB_L, SPB_R		SPA, SPA1, SPA2, SPA3, SAP, SA4, SPBA, SPBA1, SAPB
WPE	SC_L, SC_R, SC_T, SC_B ENX_L, ENX_R, ENY_T, ENY_B, R	X I.	SCA, SCB, SCC ENX, ENX1, ENY, ENY1, ENY2, REX,
BE (D-CESL)	RX_R, RY_T, RY_B	-	REY
OSE	SFAX_L, SFAX_R, SFY_T, SFY_B		SODX, SODX1, SODX2, SA5, SA6, SODY
			<u> </u>

 OSE (OD Spacing Effect) parameters are adjustable in CDF for callback calculation

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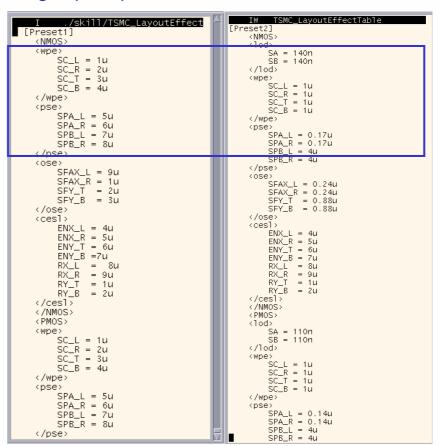
## **Preset Option**



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- Preset function is provided for customer's predefined parameters
- TSMC utility is provided for user selecting different groups of preset.



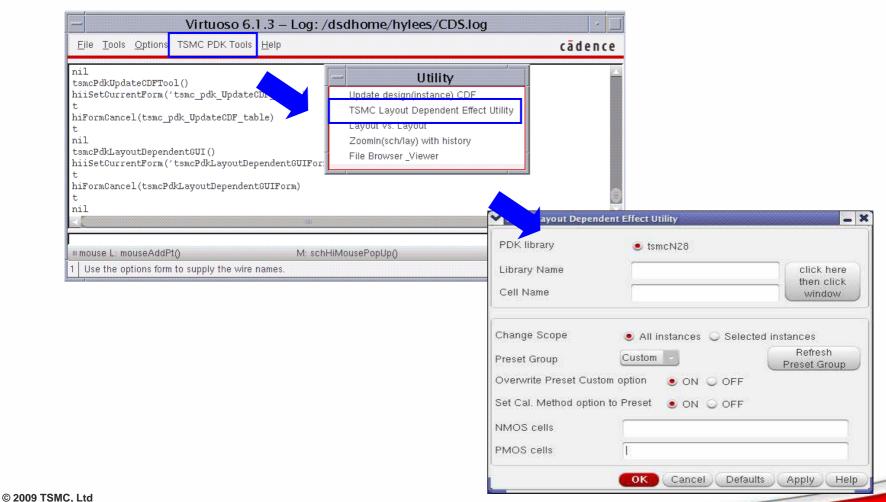
Preset1 table

Preset2 table

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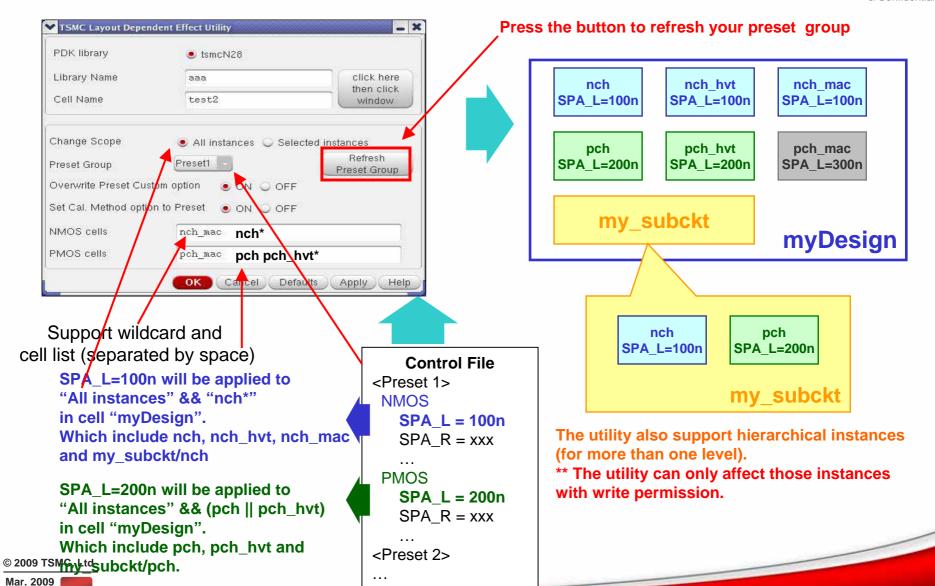


# TSMC PDK Tools-Layout Dependent Effect Utility



### **Specification of Layout Dependent Effect Utility**





Specification of Layout Dependent Effect Utility (Cont.)



& Confidential

TSMC Layout Dependent Effect Utility PDK library tsmcN28 Library Name click here aaa then click Cell Name test2 window Change Scope All instances
 Selected instances Preset1 Preset Group Preset Group Overwrite Preset Custom option ON OFF Set Cal. Method option to Preset ON OFF NMOS cells nch mac nch\* PMOS cells pch mac pch pch hvt\*

Cancel

OK

Defaults

Apply (

nch\_hvt
SPA\_L=100n

pch
SPA\_L=200n

pch\_hvt
SPA\_L=200n

pch\_hvt
SPA\_L=200n

pch\_mac
SPA\_L=300n

my\_subckt

my\_Design

SPA\_L=100n will be applied to "Selected instances" && "nch\*" in cell "myDesign". Which include nch, nch\_hvt

SPA\_L=200n will be applied to "Selected instances" && (pch || pch\_hvt) in cell "myDesign".
Which include pch, pch hvt.

Control File

<Preset 1>
NMOS

SPA\_L = 100n

SPA\_R = xxx
...

PMOS

SPA\_L = 200n

SPA\_R = xxx
...

<Preset 2>

The control file is put at the skill directory named "TSMC\_LayoutEffectTable". Hint, there are no limit for preset group.

Only apply the change to those instances

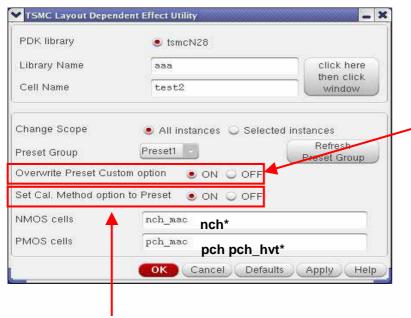
that selected by mouse.

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### **Specification of Layout Dependent Effect Utility** (Cont.)



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For example, When you turn on this option, This utility will change all Cal. Method CDF options to "Preset".

**Enable to reset "Cal. Method option" to Preset** 

Enable to overwrite the preset option when the original preset option of a instance is "Custom"

For example, When you turn off this option, This utility will not change the following instance since Its preset option is "Custom"

Display LOD Effect	● O <sup>F</sup> F ⊎ ON	off
Previous pre-set	Prevet2	off 🔽
pre-set-Option	Custom 🔽	off 🔻
Display Well Proximity Effect		off
Well Proximity Effect Cal. Method	→ Model → auto → custom ● PreSet	off
Gate_to_Left_NWell_Enc(SC_L) (M)	lu M	off 🔽
Gate_to_Right_NWell_Enc(SC_R) (M)	1u M	off 🔽
Gate_to_Top_NWell_Enc(SC_T) (M)	2u M	off -
Gate_to_Bottom_NWell_Enc(SC_B) (M)	1u M	off

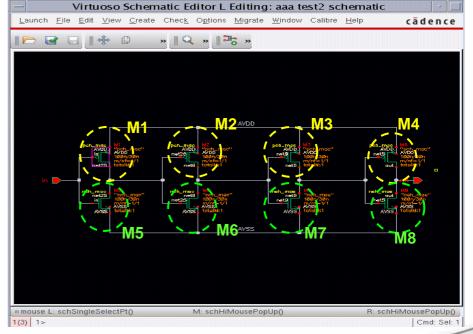
# Example 1: Setting LDE parameters of driver by "All instances"



<u>File Edit View D</u> esign Mana	iger <u>H</u> elp	cādence
	Show Files	
Library	Cell	View
aaa	test2	schematic
aaa analogLib basic cdsDefTechLib tsmcN32	test2	schematic

NMOS LDE parameters set to "Preset1" (M1~M4)
PMOS LDE parameters set to "Preset1" (M5~M8)

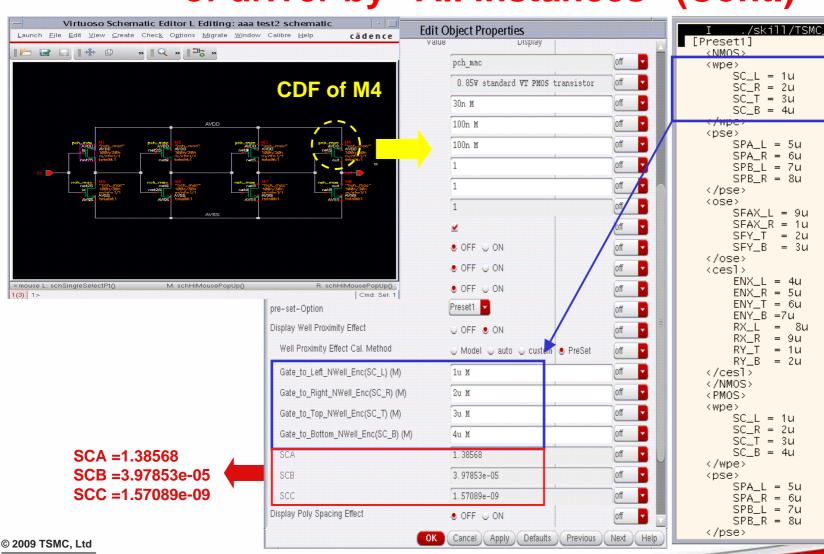
PDK library	tsmcN28	
Library Name	aaa	click here
Cell Name	test2	then click window
Change Scope Preset Group	Preset1	lected instances Refresh Preset Group
Preset Group Overwrite Preset Cu	Preset1	Refresh Preset Group F
TOTAL TOTAL COMMON	Preset1	Refresh Preset Group F



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# **Example 1: Setting LDE parameters** of driver by "All instances" (Cont.)





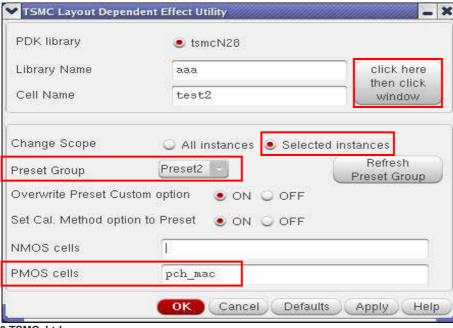
```
skill/TSMC_LayoutEffect/
```

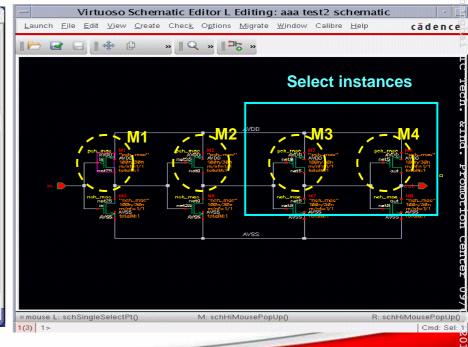
# Example 2: Setting LDE parameters of driver by "Select instances"





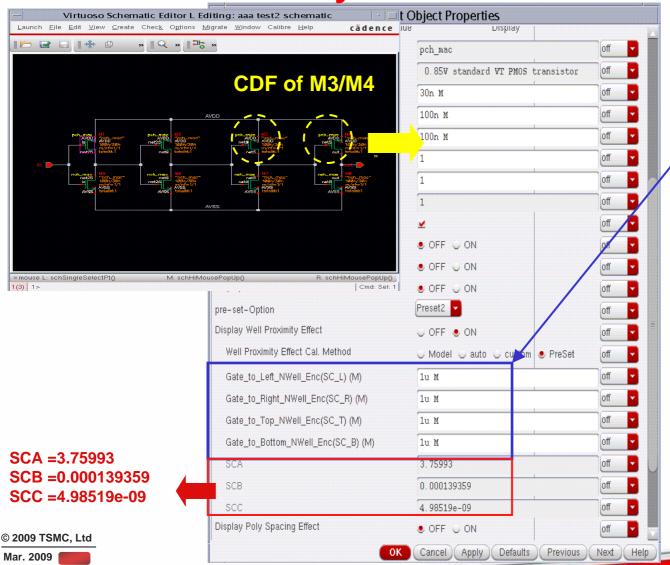
PMOS LDE parameters set to "Preset2" (M3~M4)







**Example 2: Setting LDE parameters of driver by "Select instances" (Cont.)** 



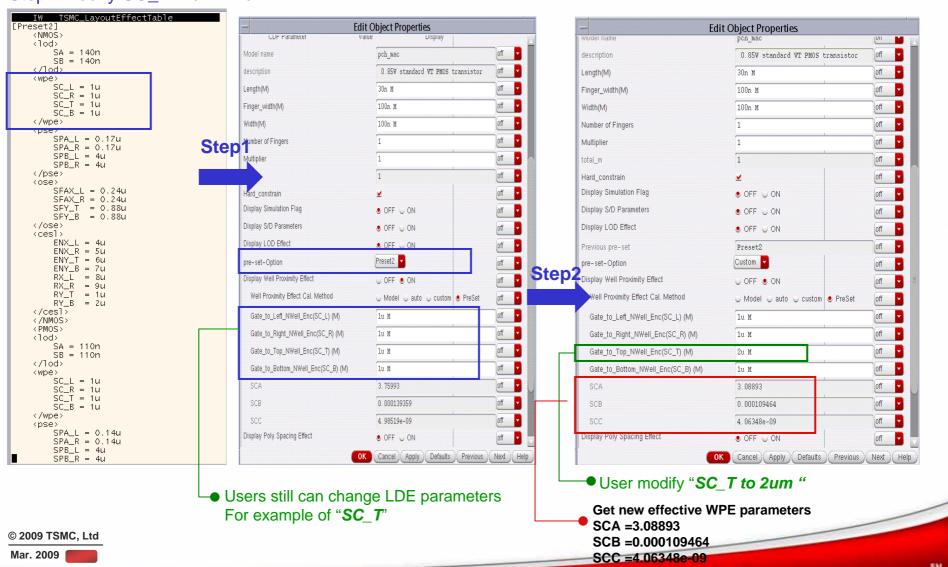
```
IW TSMC LavoutEffectTable
[Preset2]
   <NMOS>
   <lod>
       SA = 140n
       SB = 140n
   </1od>
       SC_L = 1u
       SC_R = 1u
       SC_T = 1u
       SC_B = 1u
   </wpe>
       SPA_L = 0.17u
       SPA_R = 0.17u
       SPB_L = 4u
       SPB_R = 4u
       SFAX_L = 0.24u
       SFAX_R = 0.24u
       SFY_T = 0.88u
       SFY_B = 0.88u
   </ose>
   <ces1>
       ENX_L = 4u
       ENX_R = 5u
       ENY T = 6u
       ENY B = 7u
        RX L = 8u
        RX_R
            = 9u
       RY_T = 1u
        RY_B = 2u
    </cesl>
    </NMOS>
    < PMOS>
   <1od>
       SA = 110n
       SB = 110n
   </1od>
       SC_L = 1u
       SC_R = 1u
       SC_T = 1u
       SC_B = 1u
       SPAL = 0.14u
       SPA_R = 0.14u
       SPB L = 4u
       SPB_R = 4u
```

# Example 3: Record the history of modification



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Step1:TSMC preset LDE table of "Preset2" Step2:Modify SC\_T=1u => 2u

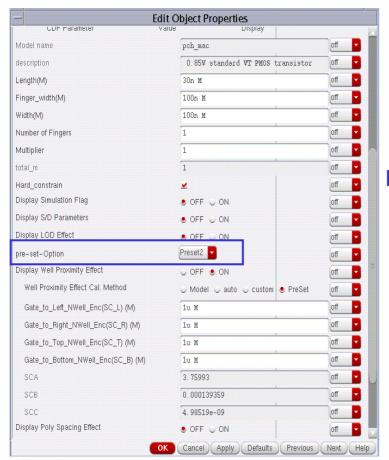


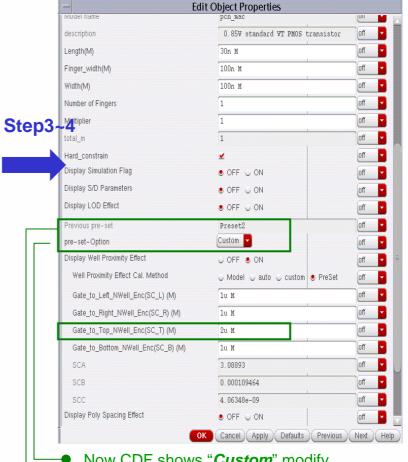
# **Example 3: Record the history of modification** (Cont.)



Step3: CDF shows *pre-set-Option* has been modified by custom

Step4: CDF records original LDE parameters from "Preset2"





Now CDF shows "Custom" modify

Record the previous "pre-set" table from Preset2

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